

Abstract

The invention relates to a sputter arrangement with a magnetron and a target, with the magnetron and the target being movable relative to one another. The magnetron comprises a magnet system, which forms a quasi-rectangular plasma tube, whose two longitudinal sides have a distance C from one another. If target and magnet system are moved relative to one another by a path corresponding approximately to the distance C , the magnet system is laid out such that the width at the end of the plasma tube is smaller or equal to the diameter of the plasma tube. However, if the path of the relative movement is less than C , the magnet system is laid out such that the width d of the ends of the plasma tube is less or equal to twice the diameter of the plasma tube.